

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants	:	Kazuhide HASEBE, et al.	Confirmation No.: 6774
U.S. Serial No.	:	10/552,262	
Filed	:	October 5, 2005	
Examiner	:	Lan Vinh	
Group Art Unit	:	1792	
For	:	SILICON DIOXIDE FILM REMOVING METHOD AND PROCESSING SYSTEM	

AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed on November 20, 2008, for which the time for response is set to expire February 20, 2009, please amend the above-identified application as set forth below and consider the following remarks. Also enclosed is a Petition for a 2 month Extension of Time with the requisite fee.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 6 of this paper.